Abstracts

In Situ Thickness Monitor for Conducting Films

S.A. Khan, J.B. Farmer, R.J. Gutmann and J.M. Borrego. "In Situ Thickness Monitor for Conducting Films." 1992 MTT-S International Microwave Symposium Digest 92.3 (1992 Vol. III [MWSYM]): 1561-1564.

In-situ monitoring and control are desirable to improve yield in advanced IC fabrication processes. In this paper we propose a novel way to monitor the thickness of conducting films in-situ using a microwave reflection technique. We present results indicating the feasibility of our approach and discuss the design of the probe.

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